

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	319	(438/528).CCLS.	USPAT	OR	OFF	2005/03/09 11:07
L2	0	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and pulse and (pre-clean)	USPAT	OR	OFF	2005/03/09 10:38
L3	0	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and pulse and (clean with wafer)	USPAT	OR	OFF	2005/03/09 10:38
L4	23	("2344138") or ("3109100") or ("3576685") or ("3907616") or ("4116791") or ("4382099") or ("4385946") or ("4434036") or ("4465529") or ("4481229") or ("4500563") or ("4521441") or ("4539217") or ("4565588") or ("4697104") or ("4764394") or ("4778561") or ("4867859") or ("4871421") or ("4912065") or ("4937205") or ("4948458") or ("5061838")).PN.	USPAT	OR	OFF	2005/03/09 10:38
L5	0	4 and (clean with wafer)	USPAT	OR	OFF	2005/03/09 10:38
L6	30	("5106827") or ("5107201") or ("5271250") or ("5277751") or ("5290382") or ("5312778") or ("5354381") or ("5435881") or ("5505780") or ("5514603") or ("5520209") or ("5542559") or ("5561072") or ("5569363") or ("5572038") or ("5587038") or ("5627435") or ("5648701") or ("5654043") or ("5674321") or ("5683517") or ("5711812") or ("5718798") or ("5770982") or ("5897752") or ("5911832") or ("5935077") or ("5944942") or ("5948168") or ("5994236")).PN.	USPAT	OR	OFF	2005/03/09 10:41
L7	193	plasma and ion and (pre-clean)	USPAT	OR	OFF	2005/03/09 10:41
L8	25	plasma and ion and (pre-clean with wafer)	USPAT	OR	OFF	2005/03/09 11:06
L9	6119	plasma and ion and passivation	USPAT	OR	OFF	2005/03/09 11:07
L10	3446	plasma and ion and passivation and wafer	USPAT	OR	OFF	2005/03/09 11:07
L11	1087	plasma and ion and passivation and wafer and RF	USPAT	OR	OFF	2005/03/09 11:07

L12	563	plasma and ion and passivation and wafer and RF and bias	USPAT	OR	OFF	2005/03/09 11:07
L13	42	1 and passivation	USPAT	OR	OFF	2005/03/09 11:07
L14	34	1 and passivation and ion	USPAT	OR	OFF	2005/03/09 11:07
L15	12	1 and passivation and ion and plasma	USPAT	OR	OFF	2005/03/09 11:09
L16	1	1 and (remove with passivation) and ion and plasma	USPAT	OR	OFF	2005/03/09 11:11
L17	8	NF3 and remove and (passivation adj layer) and ion and plasma	USPAT	OR	OFF	2005/03/09 11:11
S1	24	("5711843") or ("5074456") or ("5653811") or ("6000360") or ("6392351") or ("6679981") or ("5288650") or ("5985742") or ("5994207") or ("6013567") or ("6103599") or ("6153524") or ("6155090") or ("6187110") or ("6207005") or ("6248642") or ("6265328") or ("6291313") or ("6511899") or ("6417078") or ("6528391") or ("6582999") or ("6593173") or ("6321134")).PN.	USPAT	OR	OFF	2005/03/09 10:14
S2	0	S1 and (ion adj bombardment)	USPAT	OR	OFF	2005/02/02 13:36
S3	16	S1 and (ion) and plasma	USPAT	OR	OFF	2005/02/02 13:36
S4	5	S1 and (ion) and plasma and RF	USPAT	OR	OFF	2005/02/02 13:36
S5	5	S1 and (ion) and plasma and RF and chamber	USPAT	OR	OFF	2005/02/02 13:36
S6	0	S1 and (ion) and plasma and RF and chamber and fluoride	USPAT	OR	OFF	2005/02/02 13:36
S7	0	S1 and (ion) and plasma and RF and chamber and dope	USPAT	OR	OFF	2005/02/02 13:37
S8	3	S1 and (ion) and plasma and RF and chamber and hydrogen	USPAT	OR	OFF	2005/02/02 13:37
S9	23	("2344138") or ("3109100") or ("3576685") or ("3907616") or ("4116791") or ("4382099") or ("4385946") or ("4434036") or ("4465529") or ("4481229") or ("4500563") or ("4521441") or ("4539217") or ("4565588") or ("4697104") or ("4764394") or ("4778561") or ("4867859") or ("4871421") or ("4912065") or ("4937205") or ("4948458") or ("5061838")).PN.	USPAT	OR	OFF	2005/02/02 13:38
S10	6	S9 and ion and plasma and RF	USPAT	OR	OFF	2005/02/02 13:39
S11	6	S9 and ion and plasma and RF and chamber	USPAT	OR	OFF	2005/02/02 13:39

S12	5	S9 and ion and plasma and RF and chamber and wafer	USPAT	OR	OFF	2005/02/02 13:39
S13	3	S9 and ion and plasma and RF and chamber and wafer and bias	USPAT	OR	OFF	2005/02/02 13:39
S14	30	(("5106827") or ("5107201") or ("5271250") or ("5277751") or ("5290382") or ("5312778") or ("5354381") or ("5435881") or ("5505780") or ("5514603") or ("5520209") or ("5542559") or ("5561072") or ("5569363") or ("5572038") or ("5587038") or ("5627435") or ("5648701") or ("5654043") or ("5674321") or ("5683517") or ("5711812") or ("5718798") or ("5770982") or ("5897752") or ("5911832") or ("5935077") or ("5944942") or ("5948168") or ("5994236")).PN.	USPAT	OR	OFF	2005/02/02 13:41
S15	6	S14 and ion and plasma and chamber and RF and bias	USPAT	OR	OFF	2005/02/02 13:42
S16	30	(("5994236") or ("5998933") or ("6020592") or ("6041735") or ("6050218") or ("6076483") or ("6101971") or ("6132552") or ("6150628") or ("6164241") or ("6165376") or ("6182604") or ("6237527") or ("6239553") or ("6291938") or ("6300643") or ("6305316") or ("6335536") or ("6339297") or ("6341574") or ("6348126") or ("6403453") or ("6410449") or ("6418874") or ("6433553") or ("6453553") or ("6468388") or ("6494986") or ("6514838") or ("6551446")).PN.	USPAT	OR	OFF	2005/02/02 13:45
S17	16	S16 and chamber and wafer and RF and bias and plasma	USPAT	OR	OFF	2005/02/02 13:45
S18	14	S16 and chamber and wafer and RF and bias and plasma and ion	USPAT	OR	OFF	2005/02/02 13:46
S19	5	S16 and chamber and wafer and RF and bias and plasma and (ion with implant)	USPAT	OR	OFF	2005/02/02 14:00
S20	30	(ion adj bombardment) and plasma and dopant and workpiece and chamber	USPAT	OR	OFF	2005/02/02 14:00
S21	20	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF	USPAT	OR	OFF	2005/02/02 14:00

S22	14	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias	USPAT	OR	OFF	2005/02/02 14:01
S23	0	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and fluoride	USPAT	OR	OFF	2005/02/02 14:01
S25	11	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and dielectric	USPAT	OR	OFF	2005/02/25 17:04
S26	10	(ion adj bombardment) and plasma and dopant and workpiece and chamber and (RF adj bias)and voltage and generator and dielectric	USPAT	OR	OFF	2005/02/25 17:17
S27	13	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator	USPAT	OR	OFF	2005/02/25 14:55
S28	3	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and (low adj frequency)	USPAT	OR	OFF	2005/02/25 14:55
S29	24	("5711843") or ("5074456") or ("5653811") or ("6000360") or ("6392351") or ("6679981") or ("5288650") or ("5985742") or ("5994207") or ("6013567") or ("6103599") or ("6153524") or ("6155090") or ("6187110") or ("6207005") or ("6248642") or ("6265328") or ("6291313") or ("6511899") or ("6417078") or ("6528391") or ("6582999") or ("6593173") or ("6321134")).PN.	USPAT	OR	OFF	2005/02/25 14:55
S30	1	S29 and (low adj frequency)	USPAT	OR	OFF	2005/02/25 14:55
S31	1	("20030226641").PN.	US-PGPUB; USPAT	OR	OFF	2005/02/25 15:35
S32	1	("20040149218").PN.	US-PGPUB; USPAT	OR	OFF	2005/02/25 15:35
S33	1	(ion adj bombardment) and plasma and dopant and workpiece and chamber and (RF adj bias)and voltage and generator and dielectric and passivation	USPAT	OR	OFF	2005/02/25 15:43

S34	23	(("2344138") or ("3109100") or ("3576685") or ("3907616") or ("4116791") or ("4382099") or ("4385946") or ("4434036") or ("4465529") or ("4481229") or ("4500563") or ("4521441") or ("4539217") or ("4565588") or ("4697104") or ("4764394") or ("4778561") or ("4867859") or ("4871421") or ("4912065") or ("4937205") or ("4948458") or ("5061838")).PN.	USPAT	OR	OFF	2005/02/25 16:38
S35	3	S34 and passivation	USPAT	OR	OFF	2005/02/25 15:44
S36	24	((("5711843") or ("5074456") or ("5653811") or ("6000360") or ("6392351") or ("6679981") or ("5288650") or ("5985742") or ("5994207") or ("6013567") or ("6103599") or ("6153524") or ("6155090") or ("6187110") or ("6207005") or ("6248642") or ("6265328") or ("6291313") or ("6511899") or ("6417078") or ("6528391") or ("6582999") or ("6593173") or ("6321134")).PN.	USPAT	OR	OFF	2005/02/25 16:31
S37	0	S36 and passivation	USPAT	OR	OFF	2005/02/25 16:31
S38	6	(ion adj bombardment) and plasma and dopant and workpiece and chamber and (RF adj bias)and voltage and generator and dielectric and clean	USPAT	OR	OFF	2005/02/25 16:38
S39	9	(ion adj bombardment) and plasma and dopant and workpiece and chamber and (RF adj bias)and voltage and generator and dielectric and mask	USPAT	OR	OFF	2005/02/25 16:38
S40	6	S34 and mask	USPAT	OR	OFF	2005/02/25 16:40
S41	3	S36 and mask	USPAT	OR	OFF	2005/02/25 16:40
S42	6	(ion adj bombardment) and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and pulse	USPAT	OR	OFF	2005/03/09 10:38
S43	9	ion and plasma and dopant and workpiece and chamber and RF and voltage and bias and generator and pulse	USPAT	OR	OFF	2005/02/25 17:06
S44	0	(ion adj bombardment) and plasma and dopant and workpiece and chamber and (RF adj bias)and voltage and generator and dielectric and burst	USPAT	OR	OFF	2005/02/25 17:17

S45	0	ion and plasma and dopant and workpiece and chamber and (RF adj bias)and voltage and generator and burst	USPAT	OR	OFF	2005/02/25 17:17
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